

SUPPORTING INFORMATION

Preparation of Nitrogen-Substituted TiO₂ Thin Film Photocatalysts by the RF Magnetron Sputtering Deposition Method and their Photocatalytic Reactivity under Visible Light Irradiation

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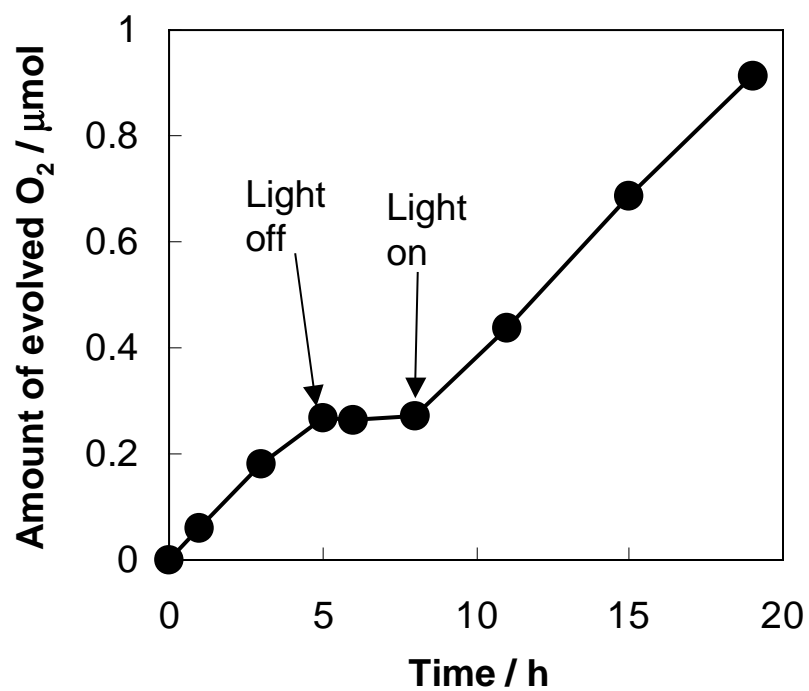


Figure S1: The reaction time profile of the photocatalytic evolution of O₂ from a 0.05 M AgNO₃ aqueous solution on Pt-loaded N-TiO₂(4) under visible light irradiation ($\lambda \geq 420$ nm).

Table S1: Surface and bulk nitrogen concentration of N-TiO₂(4) calcined at various temperatures.

Calcination temperature (K)	concentration of substituted N (%)	
	Surface ^a	Bulk ^b
before calcination	5.95	6.00
473	3.75	6.00
673	2.15	5.95
773	0.00	2.25

^aEstimated from XPS peak areas of Ti 2p and N 1s for the top surface of the N-TiO₂(4) thin films. ^bEstimated from XPS peak areas of Ti 2p and N 1s for N-TiO₂(4) thin films etched by Ar⁺ ion sputtering for 5 min.